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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10038800	FILING DATE 12/31/2001	CLASS 430	SUBCLASS 313	GAU 1756	EXAMINER <i>Dante Barreca</i>
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**APPLICANTS: Ma Ching-Tien; Chen Tsung-Chuan; Hsu Shew-Tsu;

**CONTINUING DATA VERIFIED: *None -3*

** FOREIGN APPLICATIONS VERIFIED: *None -3*

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials		<input type="checkbox"/> yes <input checked="" type="checkbox"/> no <input type="checkbox"/> yes <input checked="" type="checkbox"/> no <i>-3</i>	ATTORNEY DOCKET NO 67,200-549

TITLE : Method for forming via and contact holes with deep UV photoresist

U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drawn.	Figs. Drawn.	Print Fig.
TERMINAL DISCLAIMER		Primary Examiner		Application Examiner
		PREPARED FOR ISSUE		
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